

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

| INFORMATION DISCLOSURE CITATION IN AN APPLICATION (PTO-1449) | | | ATTY. DOCKET NO. 50432-477 | SERIAL NO. Unassigned 10/021,497 | | |
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| | | | APPLICANT William G. EN, et al. | | | |
| | | | FILING DATE Concurrently Herewith | GROUP Unassigned 2822 | | |
| U.S. PATENT DOCUMENTS | | | | | | |
| EXAMINER'S INITIALS | PATENT NO. | DATE | NAME | CLASS | SUBCLASS | FILING DATE |
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| FOREIGN PATENT DOCUMENTS | | | | | | |
| EXAMINER'S INITIALS | PATENT NO. | DATE | COUNTRY | CLASS | SUBCLASS | Translation <input type="checkbox"/> Yes <input type="checkbox"/> No |
| | | | | | | |
| OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.) | | | | | | |
|  | <p>"Ellipsometer/reflectometer for Ultra-thin Gate Oxide Metrology," October 1, 2001, http://www.ecnmag.com/ecnmag/issues/2001/10/, pg. 1 of 1</p> <p>Hitachi America, Ltd. Semiconductor Equipment Group ..., "Customizable Shallow Trench Isolation," pg. 1 of 1</p> | | | | | |
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| EXAMINER | | | DATE CONSIDERED | | <i>11/16/102</i> | |

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